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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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Application of :
Yasuhiko SUGIYAMA et al. :
Appln. No. 10/721,522 : Art Unit - 1756
Filed: November 24, 2003 : Examiner- Stephen D. Rosasco
For: PHOTOMASK CORRECTION :
METHOD USING COMPOSITE :
CHARGED PARTICLE BEAM, :
AND DEVICE USED IN THE :
CORRECTION METHOD : Docket No. S005-5168

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P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT AFTER FINAL UNDER RULE 116

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In response to the Office Action mailed June 6, 2006, applicants amend their application as follows:

ADDITIONAL FEE:

No additional fee is believed required in connection with this amendment. However, should it be determined that a fee is due, authorization is hereby given to charge any such fee to our Deposit Account No. 01-0268.

MAILING CERTIFICATE ON PAGE 6